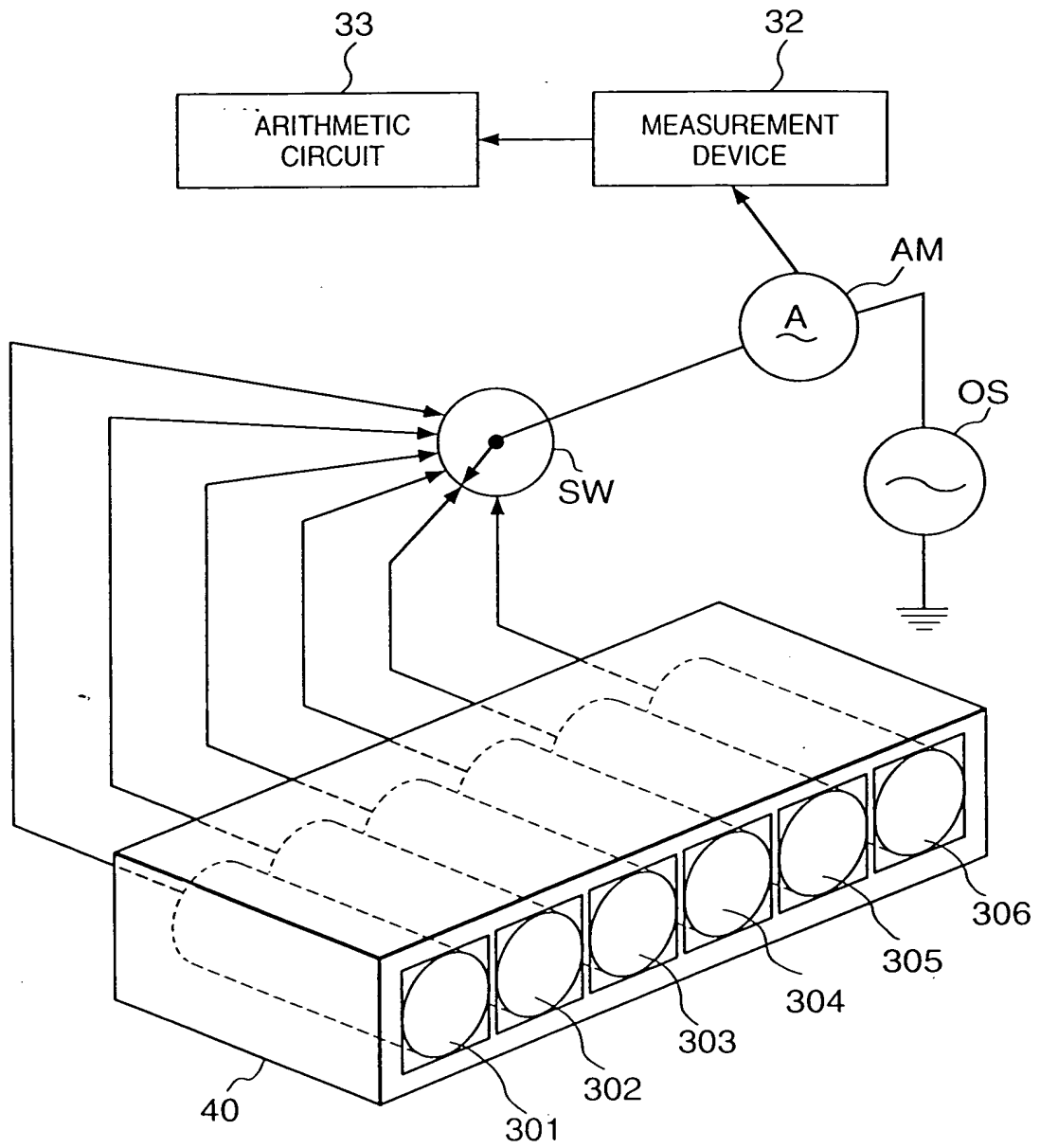


FIG. 1



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FIG. 2

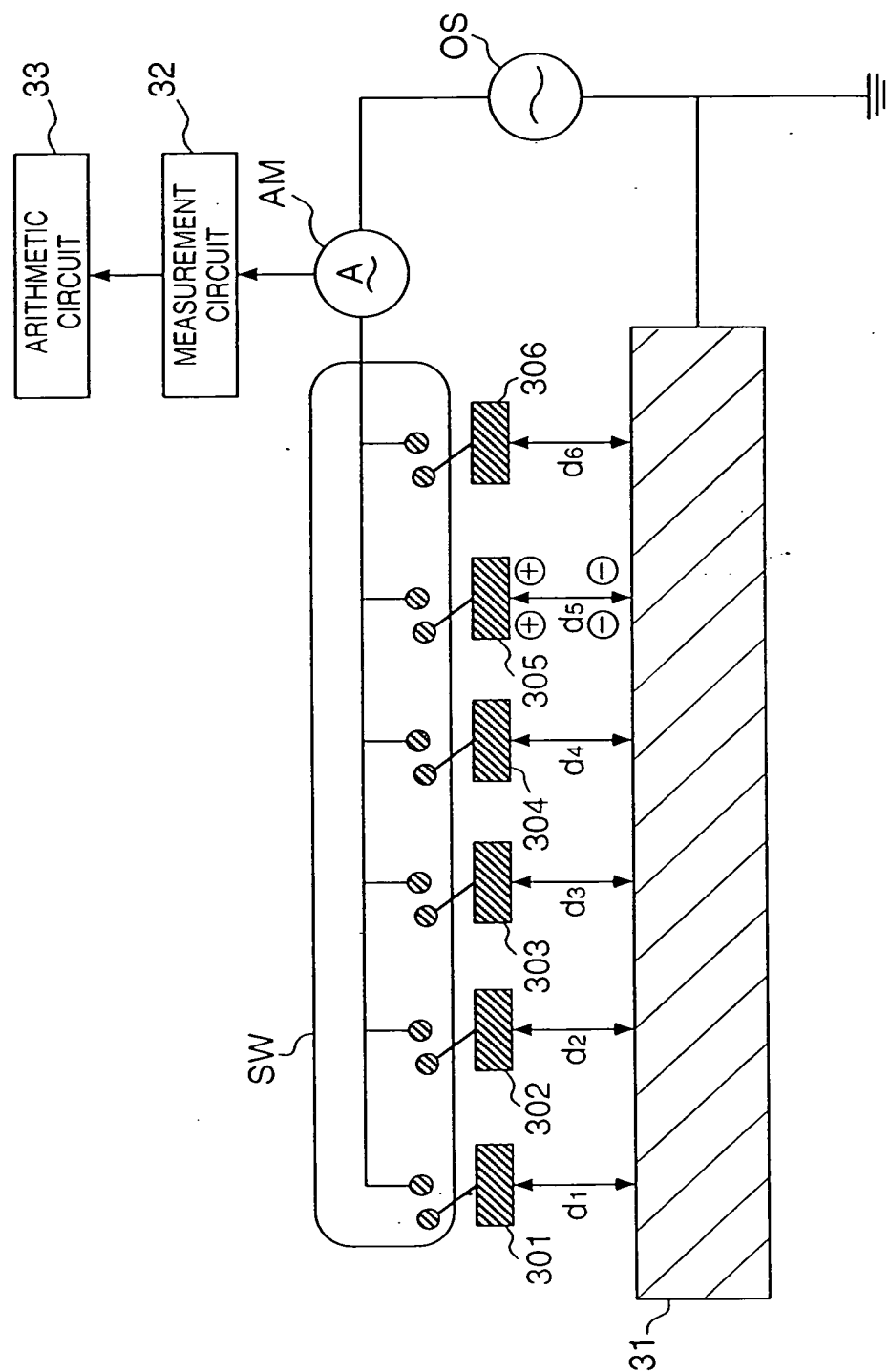


FIG. 3

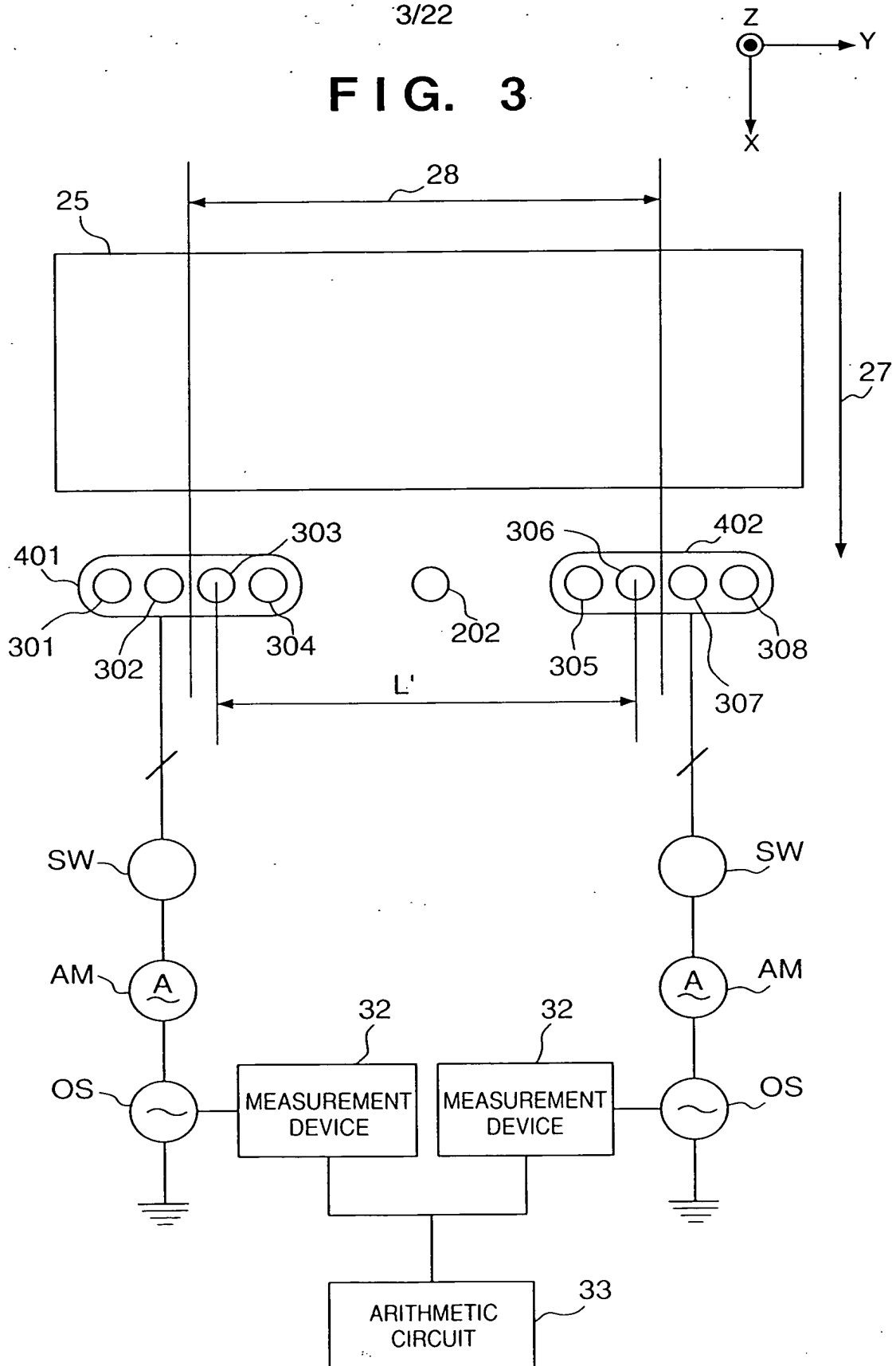


FIG. 4

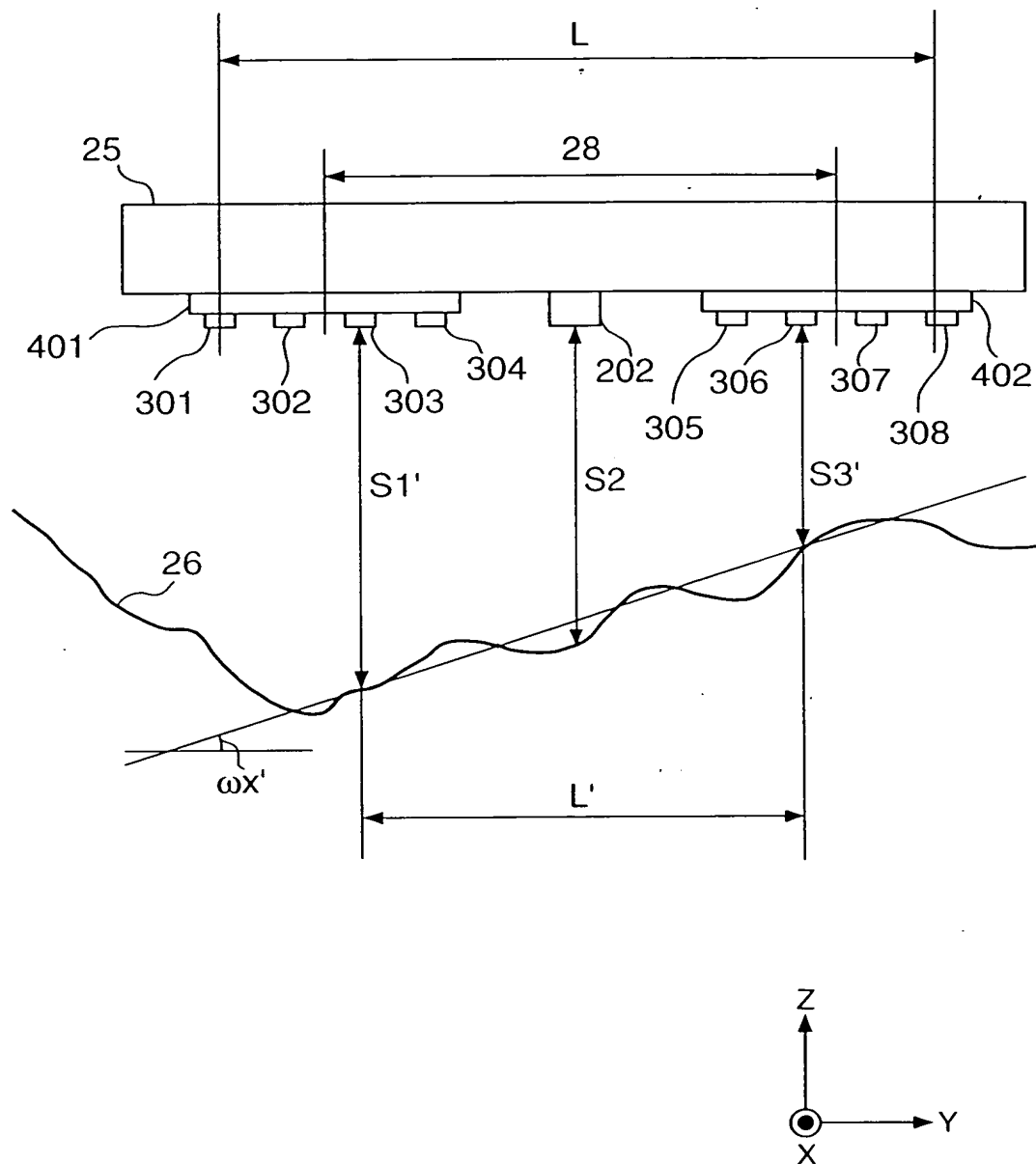
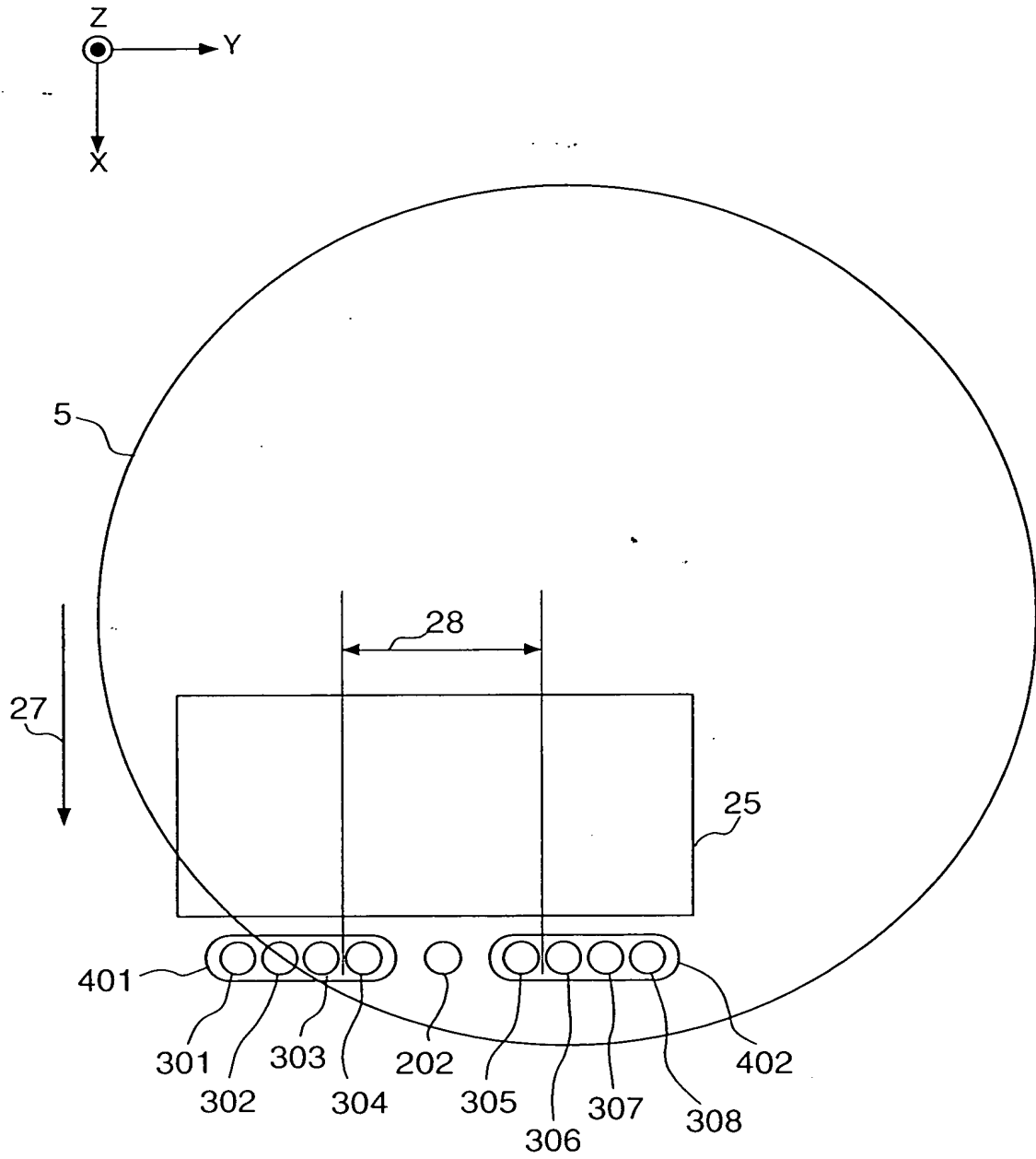


FIG. 4

FIG. 5



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FIG. 7

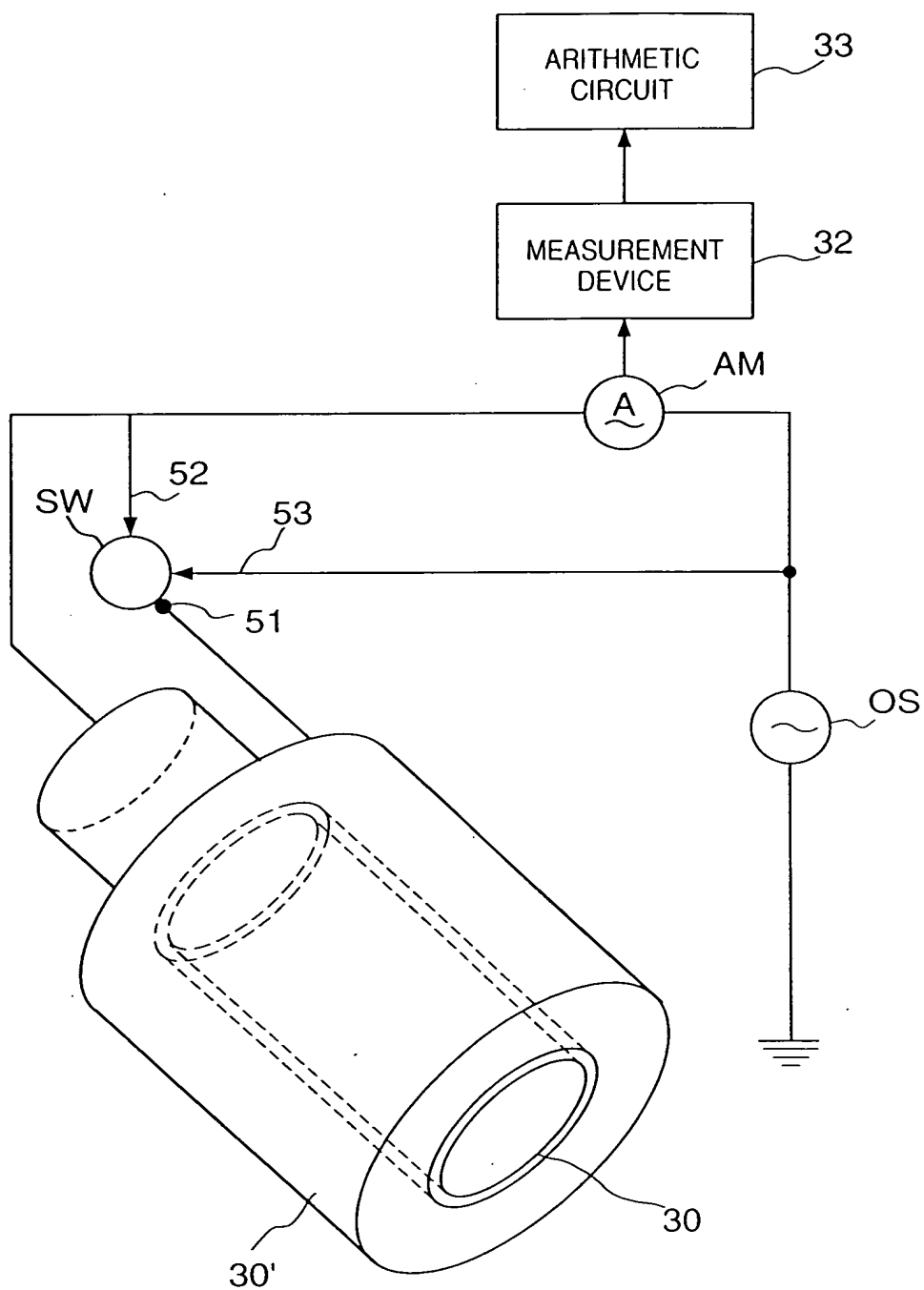
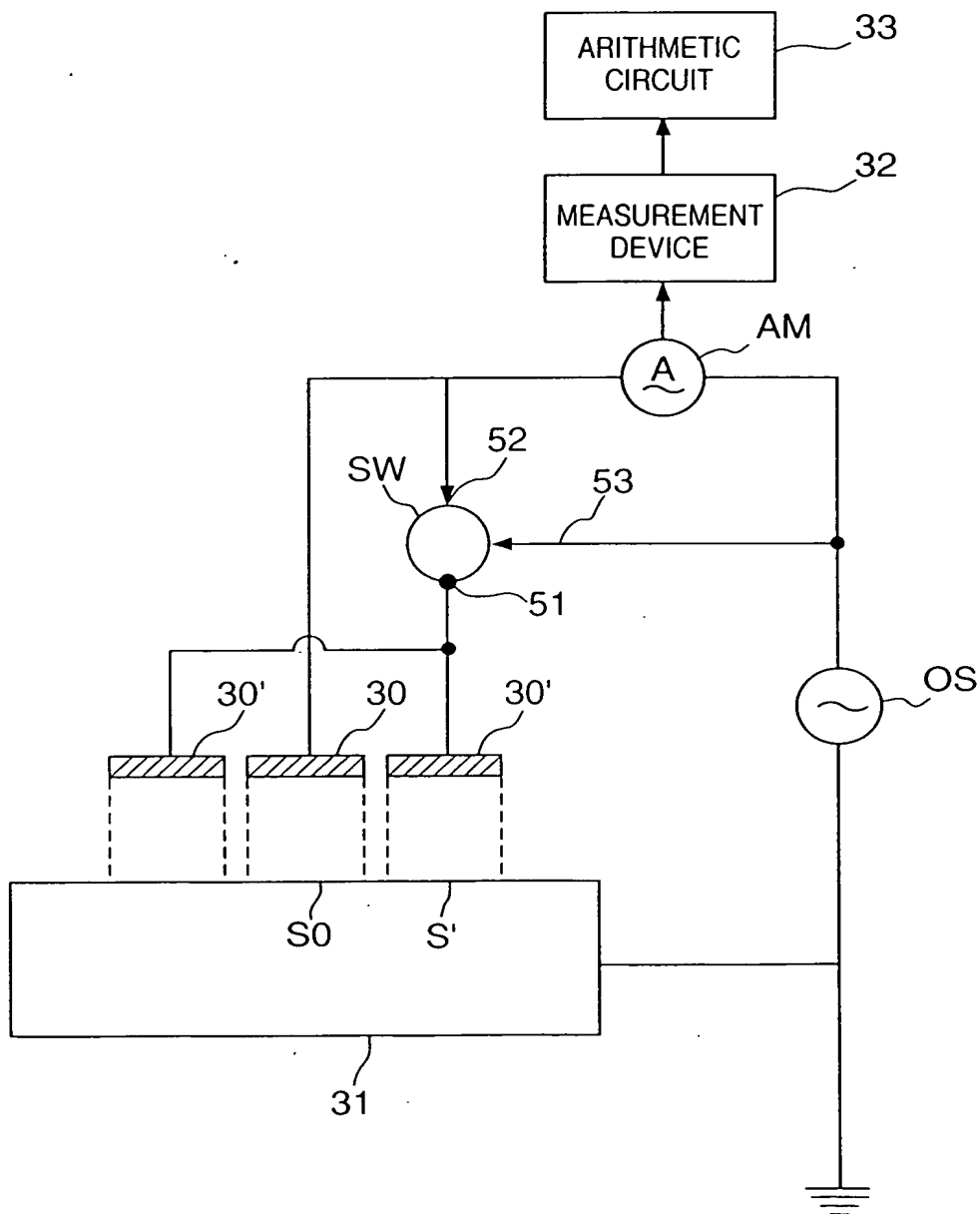


FIG. 8



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FIG. 9

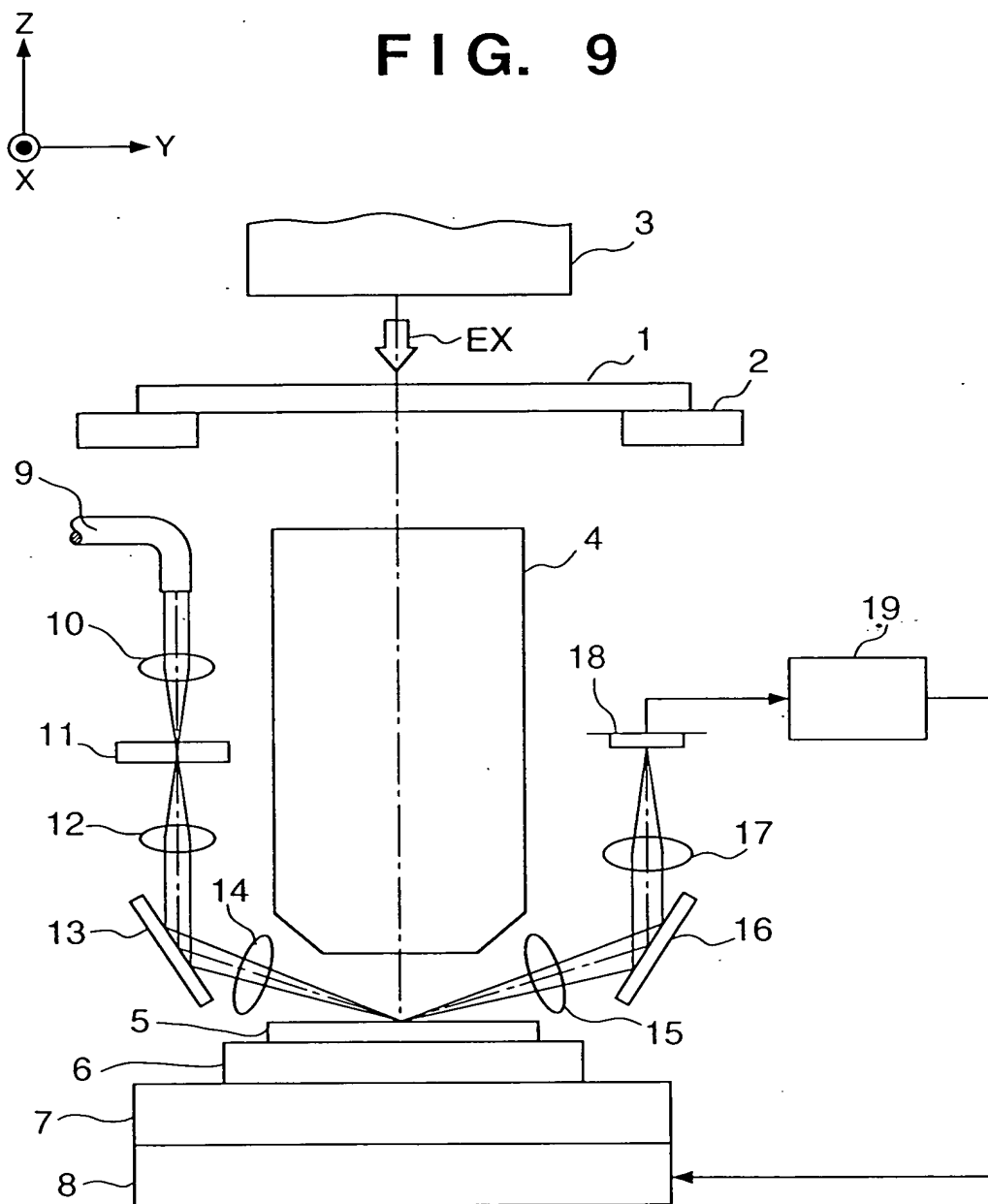


FIG. 10

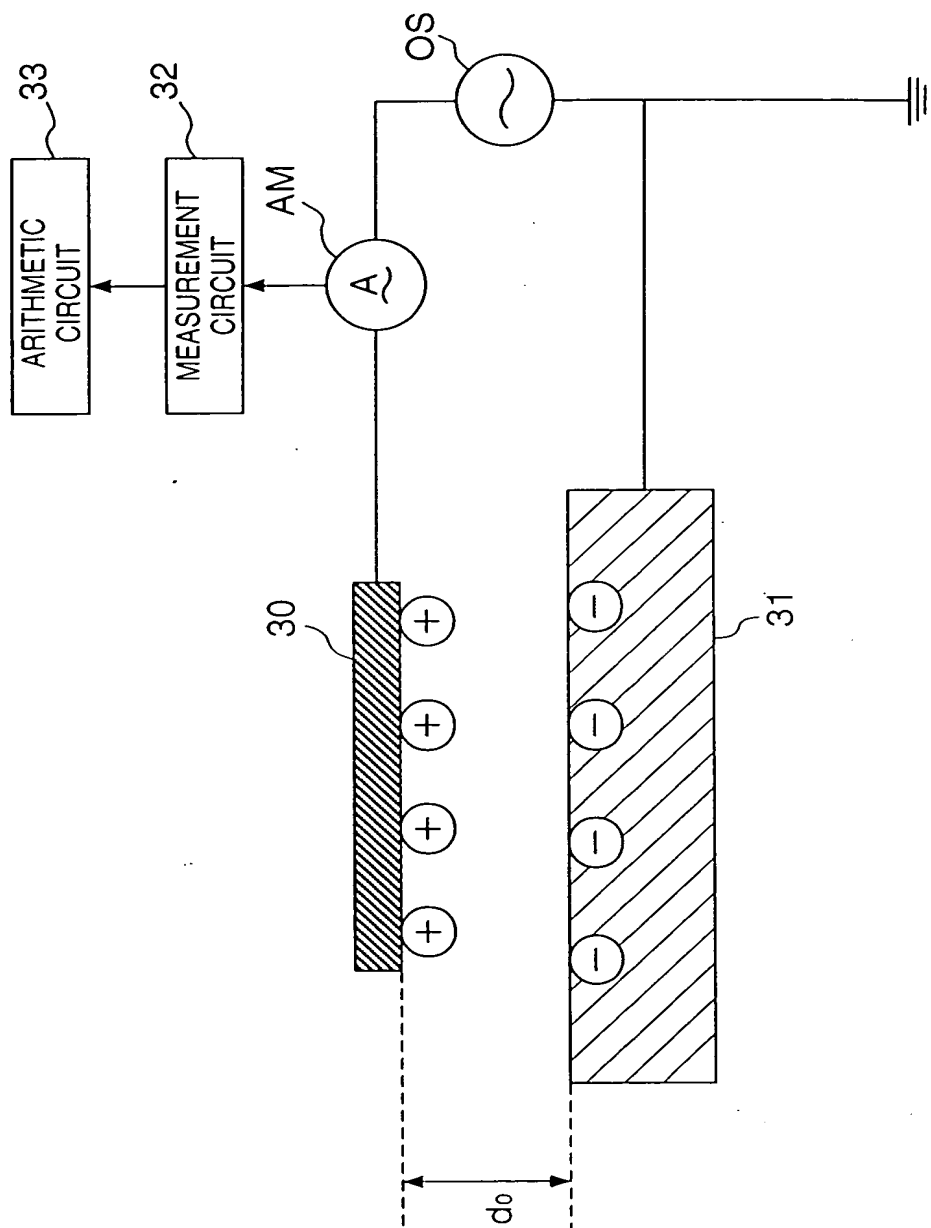
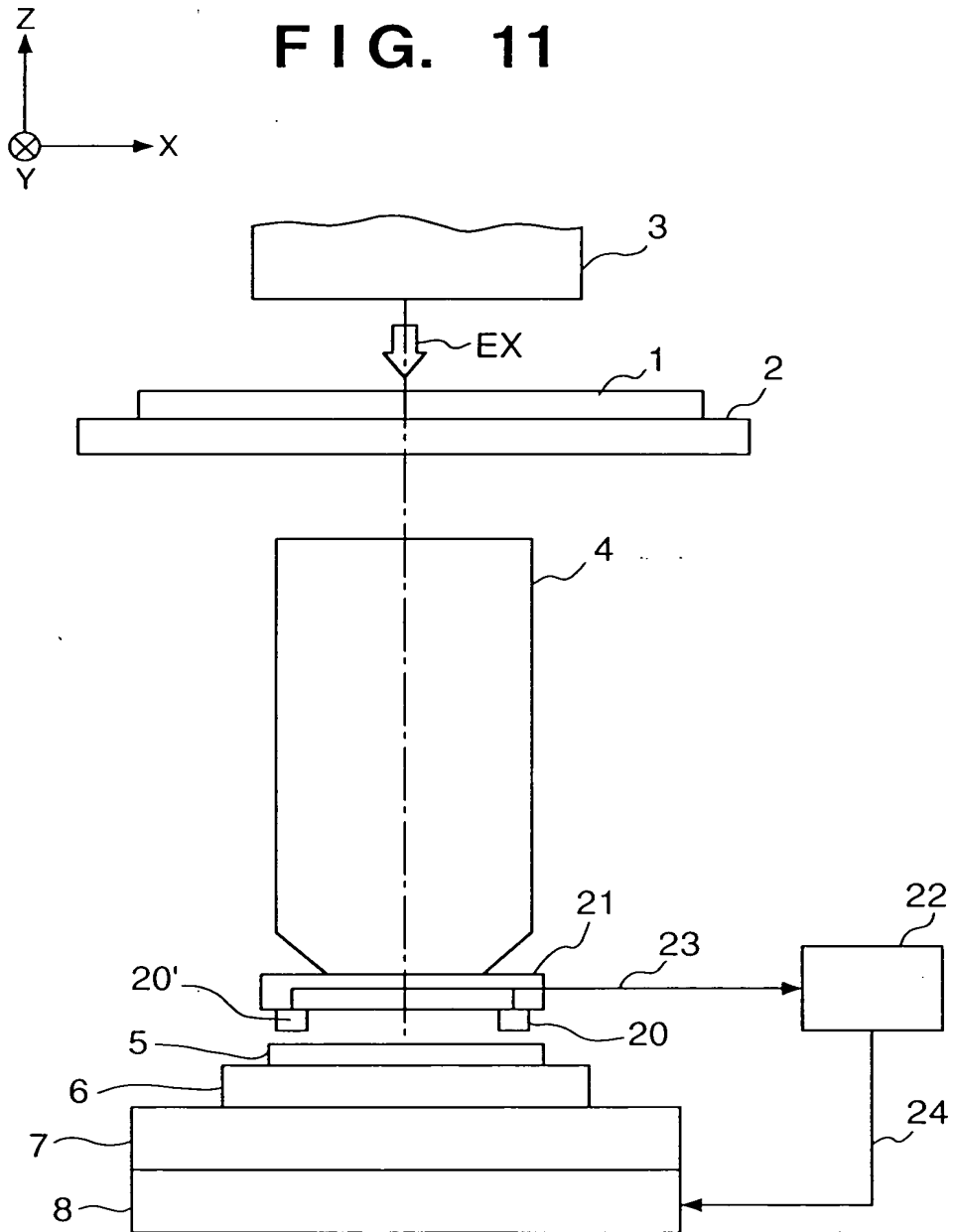


FIG. 11



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FIG. 12

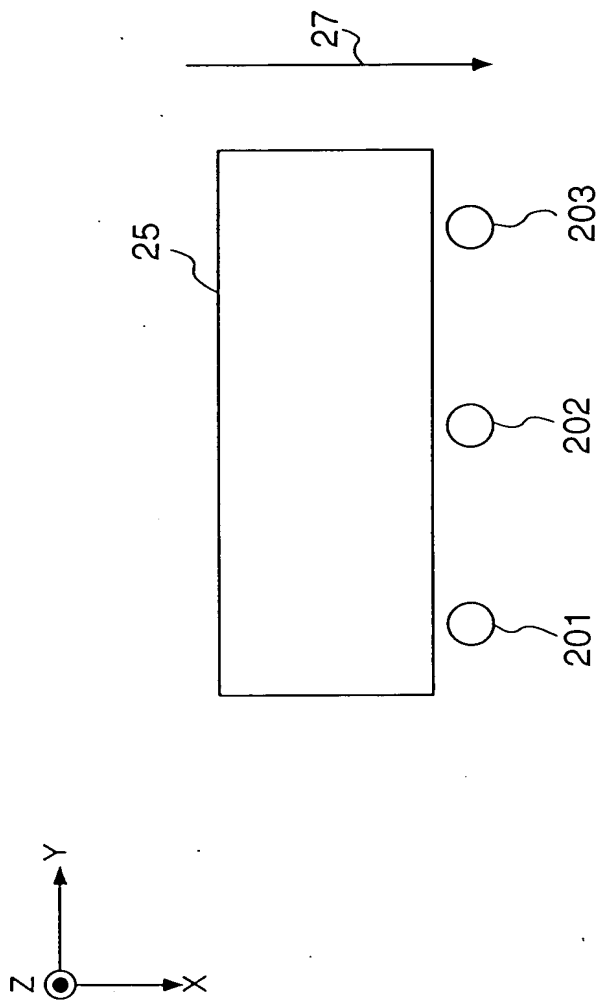


FIG. 13

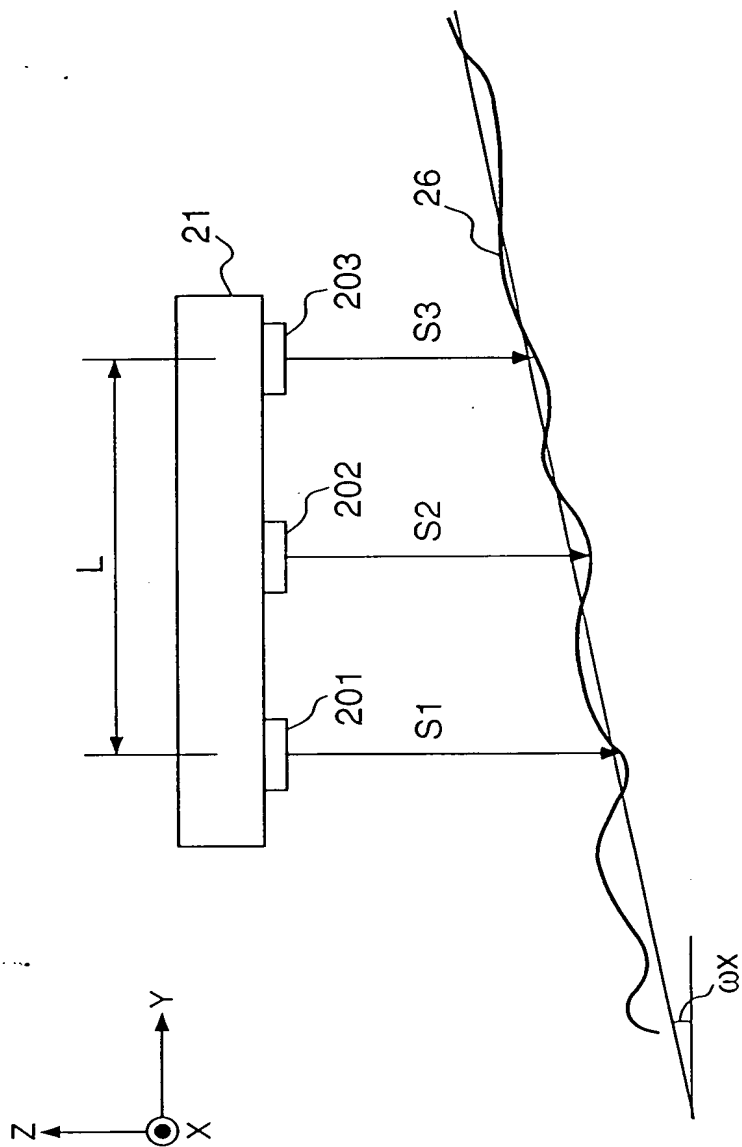


FIG. 14

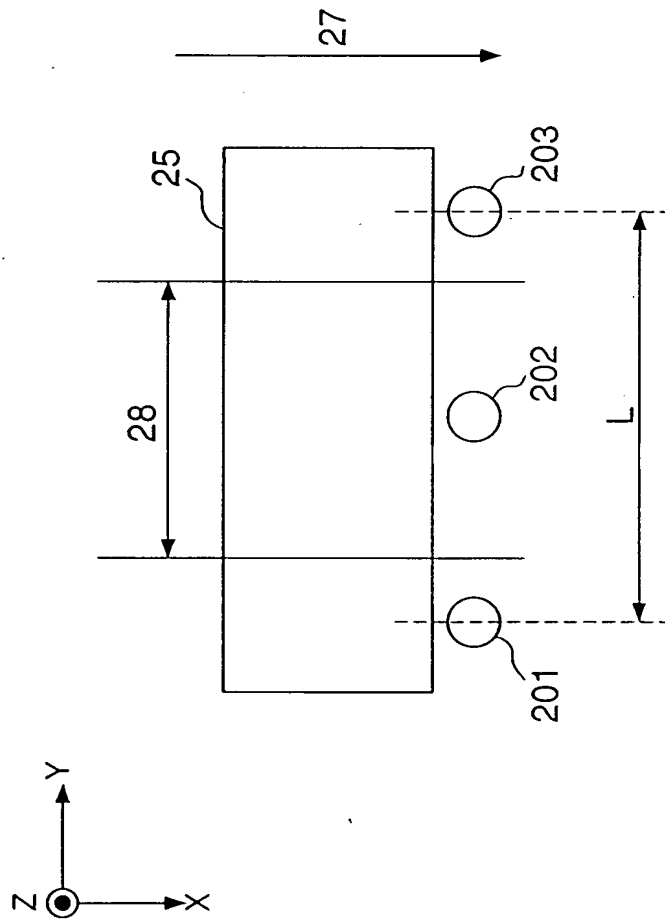
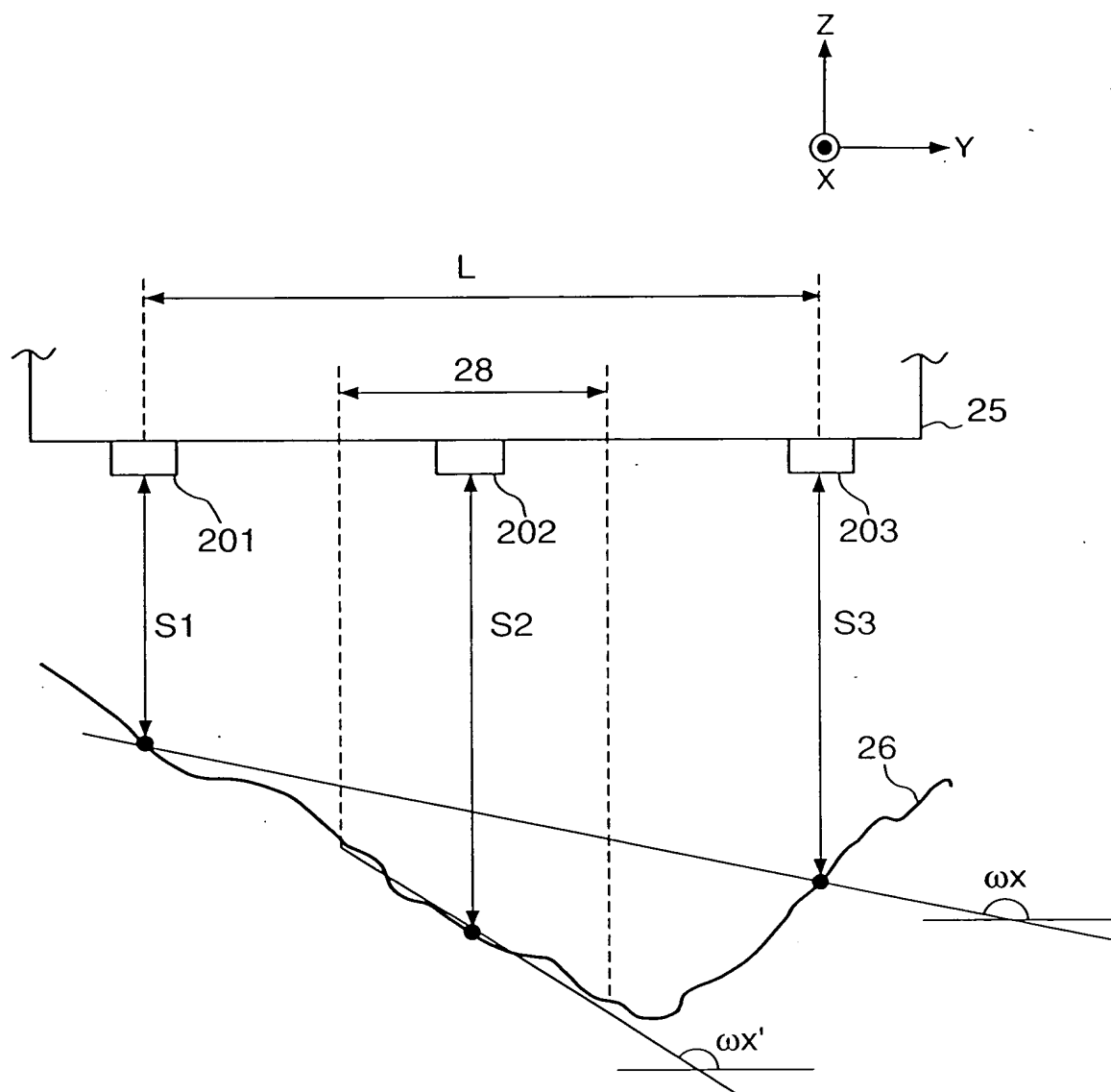


FIG. 15



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FIG. 16

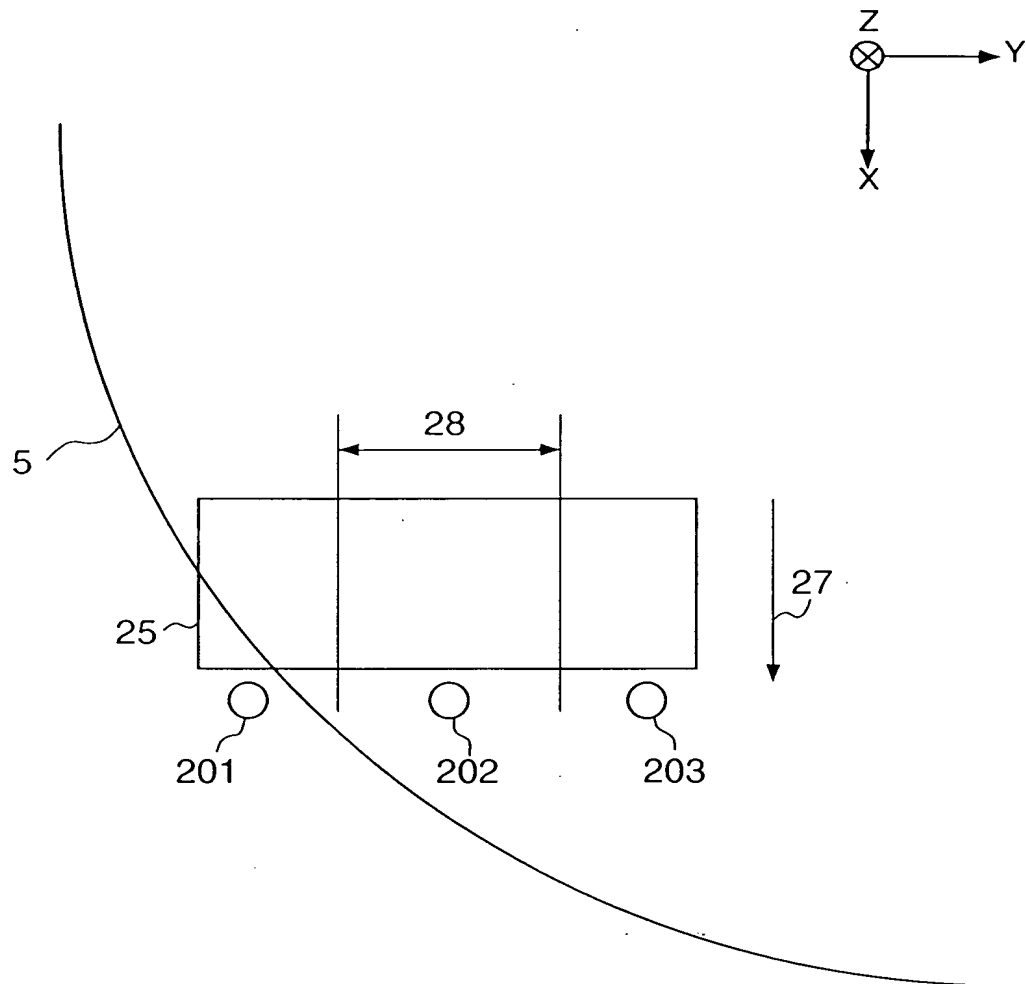
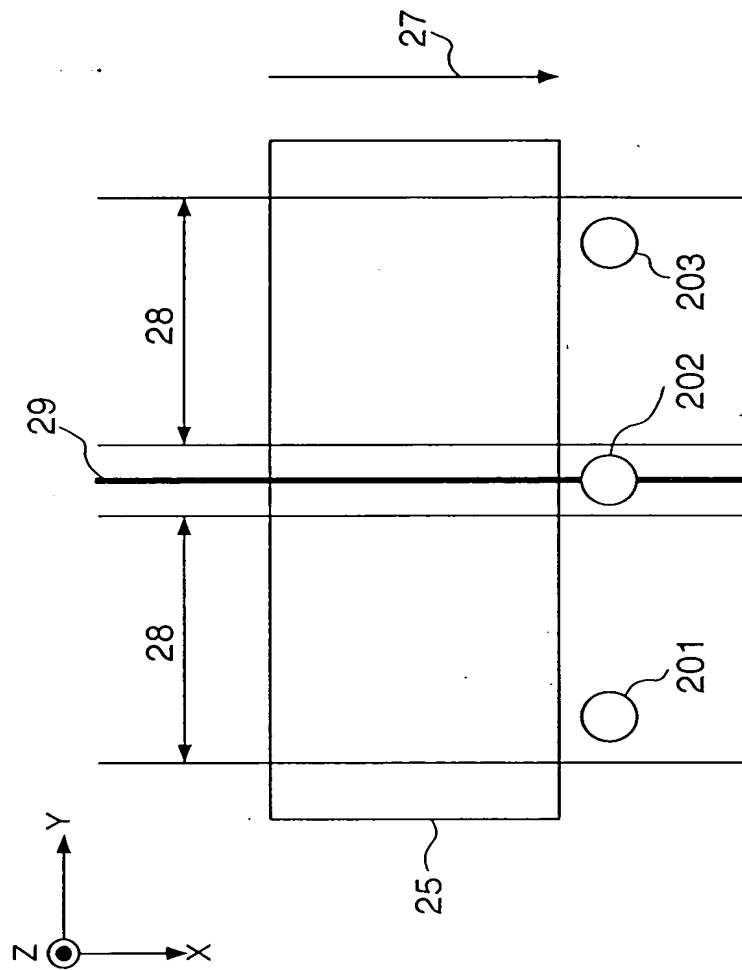


FIG. 17



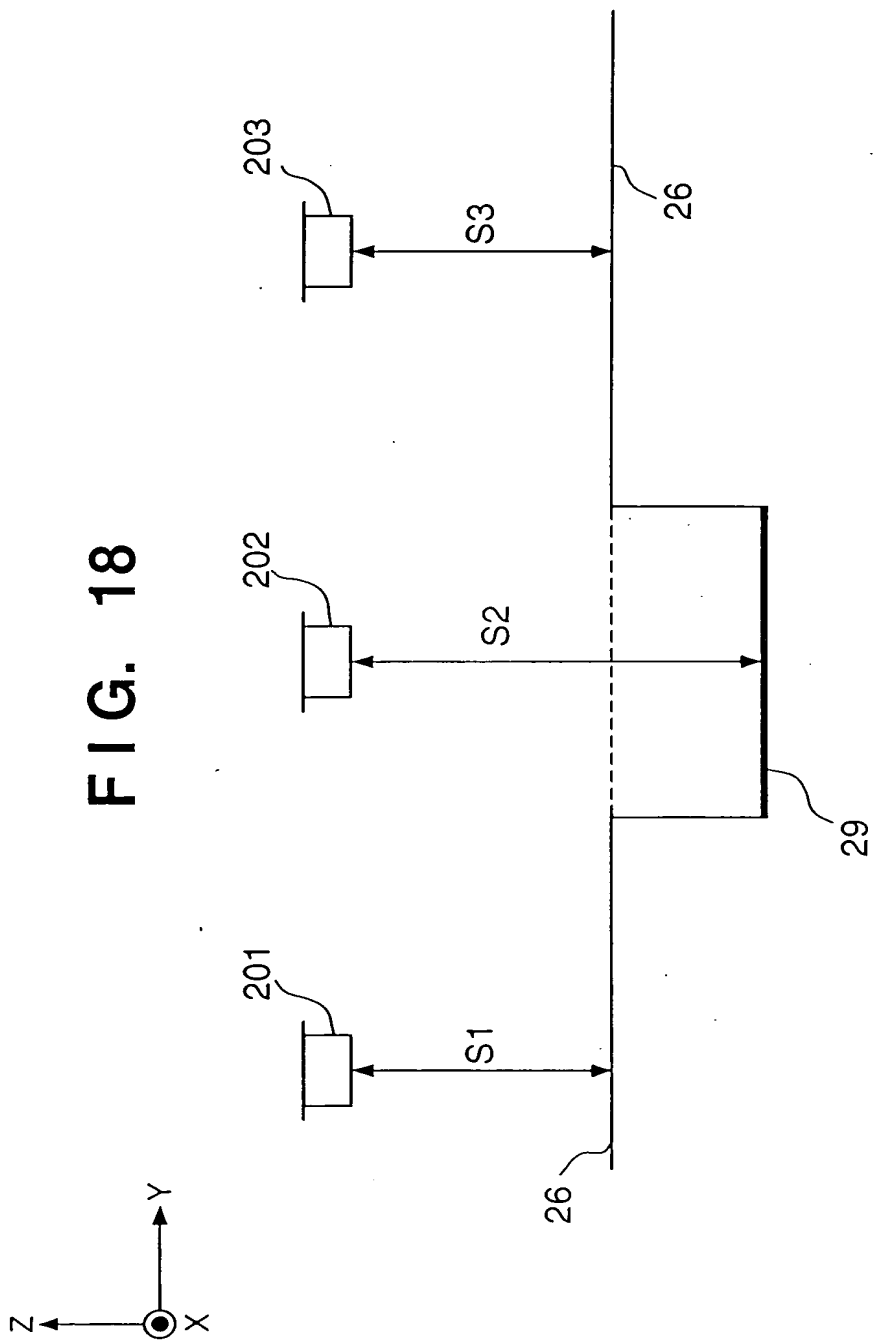
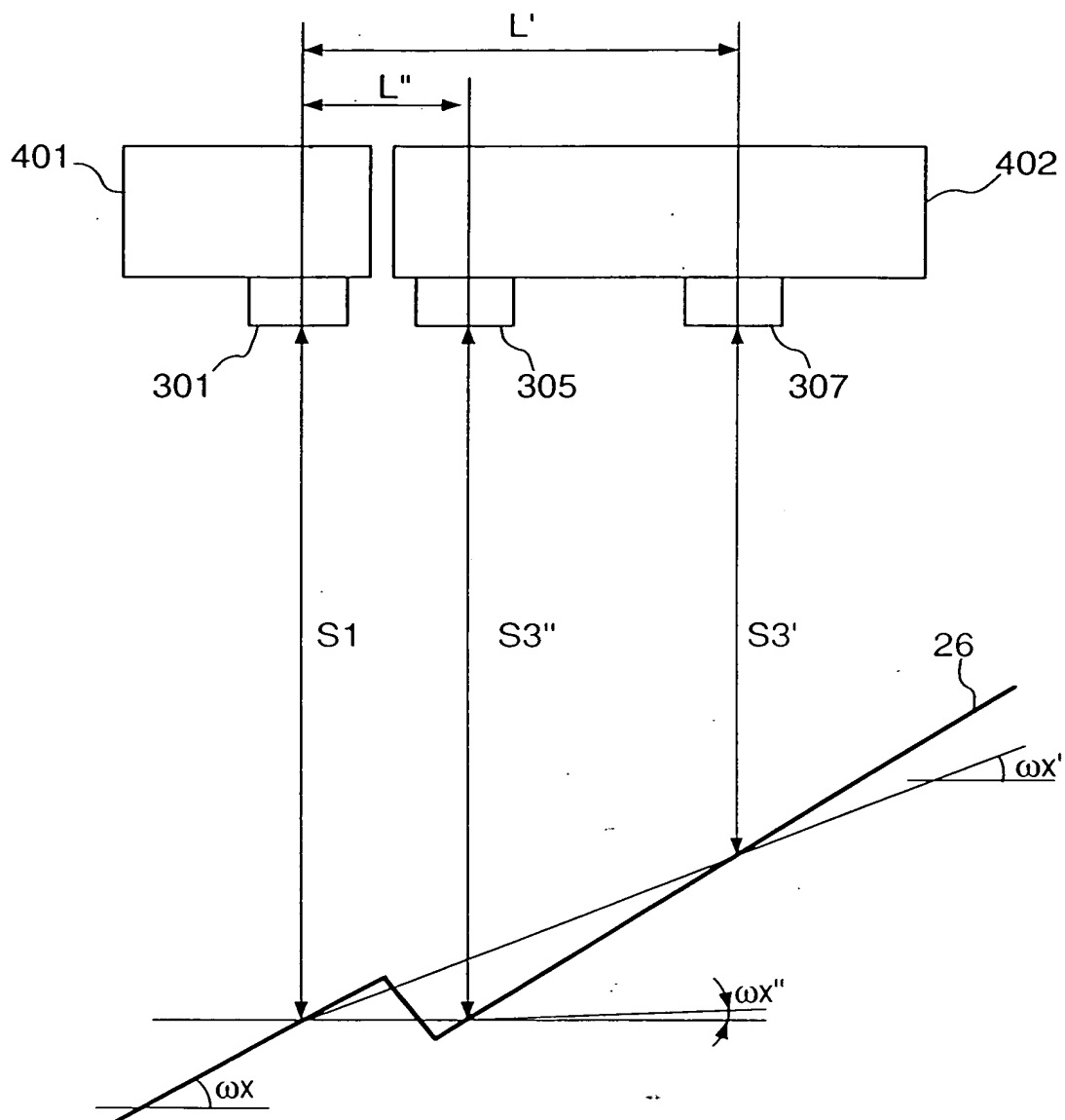


FIG. 19



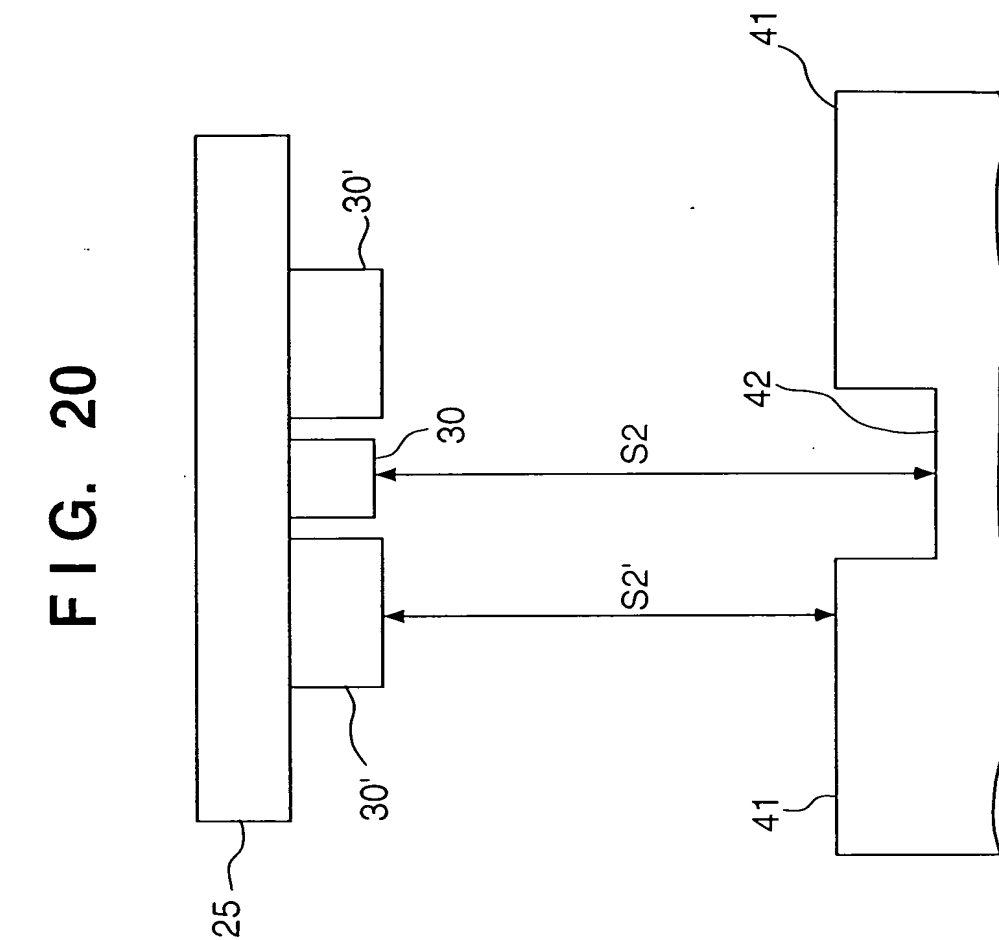
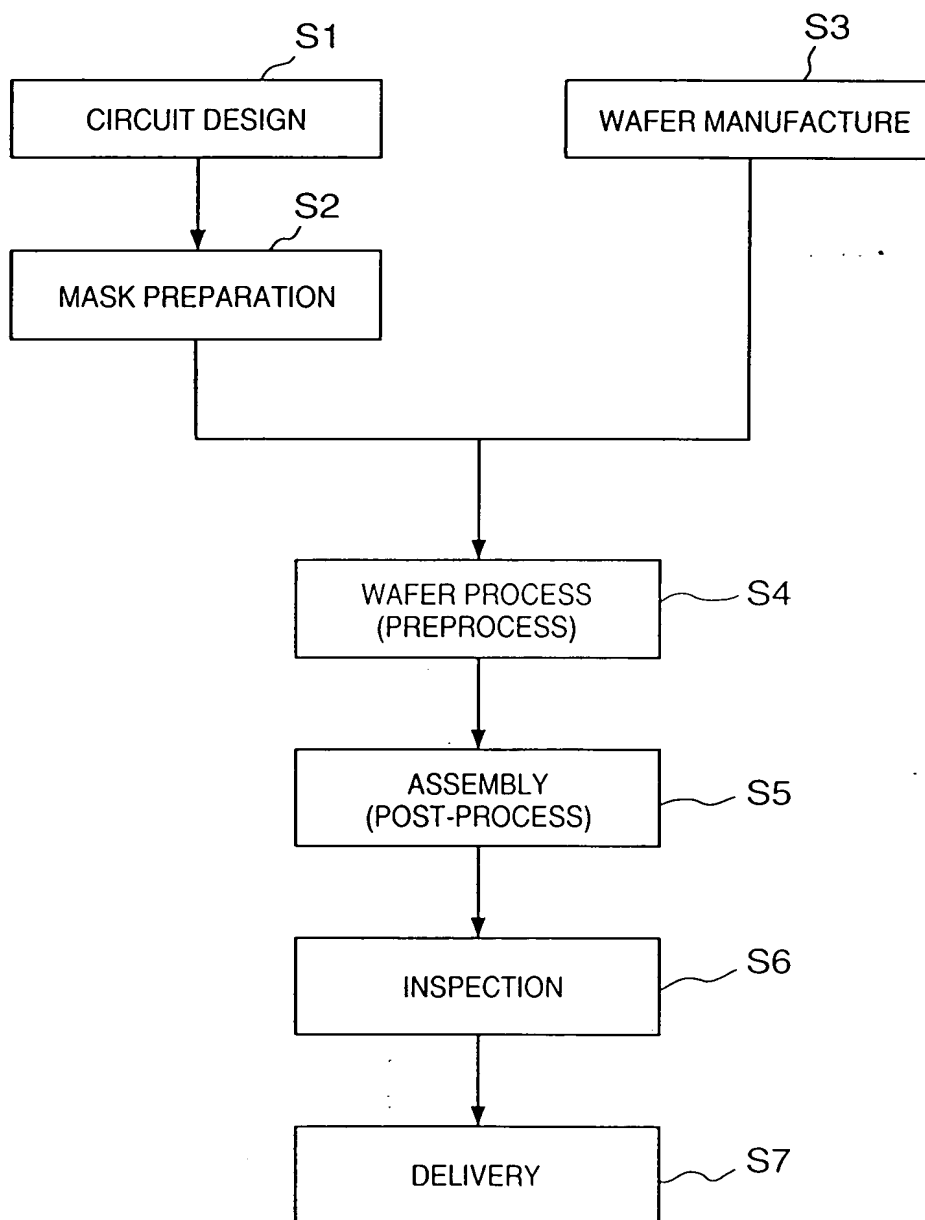


FIG. 21



SEMICONDUCTOR DEVICE MANUFACTURING FLOW

